

ABSTRACT

An inspection system (100) for inspecting a mask (101) to determine if the mask (101) has at least one desired transparent area (902) organized in a 5 desired transparent pattern (908) and at least one desired opaque area (900) organized in a desired opaque pattern (906). The mask (101) includes an actual mask pattern (103C) having at least one actual transparent area (103A) and at least one actual opaque area (103B). In one embodiment, the 10 inspection system can include a beamlet supply assembly (111) that (i) directs a shaped beamlet towards one of the actual areas (103A, 103B) of the mask (101), and/or (ii) directs a plurality of beamlets simultaneously towards the mask (101).

15

20

25

30

PATENT: PA02335-US\11269.34